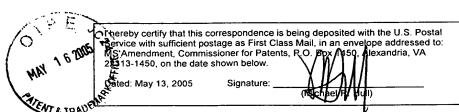
IFW



Docket No.: 29926/39505

(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Young-Soo Kim

Application No.: 10/615,038

11pp110ation 1 (0... 10/015,050

Filed: July 8, 2003

For: ATOMIC LAYER DEPOSITION OF

TITANIUM NITRIDE USING BATCH TYPE

CHAMBER AND METHOD FOR

FABRICATING CAPACITOR BY USING THE

SAME

Examiner: Bradley Smith

Confirmation No.: 3909

Art Unit: 2891

RESPONSE TO RESTRICTION REQUIREMENT

MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In response to the restriction requirement imposed in the office action mailed on April 13, 2005, applicant provisionally elects specie I (claims 1-2 and 7-8, with traverse). This application is already in prosecution and a first office action has been issued. All claims were examined in the first office action and only now, after a first examination, has a restriction been issued. In any event, applicant respectfully submits that claim 1 is allowable over all art of record and therefore an early indicating all claims being allowed and considered is respectfully requested.

Application No.: 10/615,038 Docket No.: 29926/39505

The Commissioner is authorized to charge any fee deficiency required by this paper, or credit any overpayment, to Deposit Account No. 13-2855.

Dated: May 13, 2005

Respectfully submitted,

By___

Michael Witall Registration No.:/35,902

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